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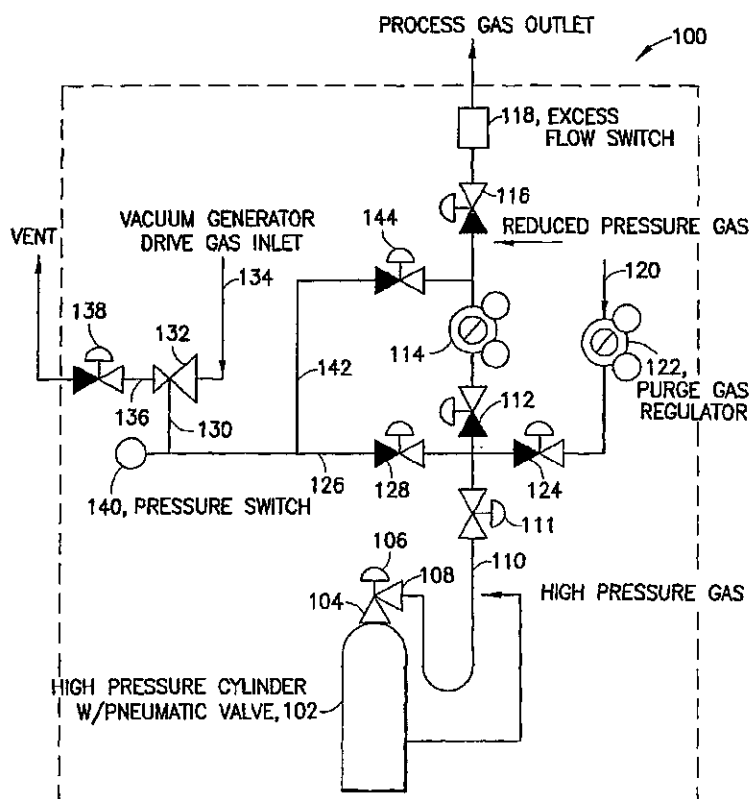
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(54) Title: PRESSURE-BASED GAS DELIVERY SYSTEM AND METHOD FOR REDUCING RISKS ASSOCIATED WITH STORAGE AND DELIVERY OF HIGH PRESSURE GASES



(57) Abstract: Apparatus and method for dispensing a gas using a gas source (102) coupled in selective flow relationship with a gas manifold (126). The gas manifold (126) including flow circuitry (110) for discharging gas to a gas-using zone, and the gas source (102) includes a pressure-regulated gas source vessel (102) containing the gas at superatmospheric pressure.